

QCKET NO. 5988-056-27

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Kenichi YOKOYAMA et al.

ART UNIT:

SERIAL NO.:

10/679,367

EXAMINER:

FILING DATE: October 7, 2003

FOR:

RADIATION-SENSITIVE RESIN COMPOSITION

FILING OF ENGLISH TRANSLATION OF APPLICATION

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

Responsive to the notification dated April 26, 2004, enclosed is the Declaration of Ippei Andoh verifying the translation of the application originally submitted in the Japanese language on October 7, 2003, in U.S. Patent Application No. 10/679,367, into English, including the translated version of the application. The required fee for submission was paid at the time of filing the application.

In light of the foregoing, this application is deemed to be in proper condition for examination and such favorable action is earnestly solicited.

Respectfully submitted,

Steven B. Kelber

Registration No. 30,073

Attorney of Record

1200 Nineteenth Street, N.W. Washington, D.C. 20036-2412 Telephone No. (202) 861-3900 Facsimile No. (202) 223-2085

Christopher W. Raimund Registration No. 47,258



DECLARATION

I, Ippei Andoh, having an address of c/o CHEMPATENT, LTD., Tamura Bldg. 5th Floor, 4-23-17, Higashi-Ikebukuro, Toshima-ku, Tokyo, Japan, hereby declare that I have competent knowledge of the Japanese and English languages, and that I have made the accompanying translation of **United States Patent Application No. 10/679,367** filed on **September 7, 2003**, and that the said translation is true and correct to the best of my knowledge and belief and that this declaration was made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code.

DECLARED by said Ippei Andoh

at Tamura Bldg. 5th Floor, 4-23-17, Higashi-Ikebukuro, Toshima-ku, Tokyo, Japan

This 24th day of February, 2004

Ippei Andoh